

reciting the features of original claim 27, from which claims 28 and 30 depended. The amendments to claims 28 and 30 do not narrow the scope of these claims.

A Claim for Priority was filed on February 2, 1999 in parent Application No. 09/219,707 with certified copies of the priority documents for this application. It is respectfully requested that the Examiner acknowledge receipt of the certified copies.

An Information Disclosure Statement with Form PTO-1449 was filed in the above-captioned patent application on August, 6, 2001. Applicant has not yet received from the Examiner a copy of the Form PTO-1449 initialed to acknowledge the fact that the Examiner has considered the disclosed information. Accordingly, the Examiner is requested to initial and return to the undersigned a copy of the Form PTO-1449. For the convenience of the Examiner, a copy of that form is attached.

In Item 3, the Office Action rejects claims 27 and 32 (the rejection of claims 28-31 having been withdrawn as a result of the personal interview) under 35 U.S.C. §102(b) as being anticipated by U.S. Patent No. 4,838,994 to Gulde et al. This rejection is respectfully traversed:

Applicant respectfully submits that independent claim 27 distinguishes over Gulde at least because Gulde fails to teach, disclose, or suggest an etching mask for selectively etching a workpiece, wherein the etching mask is made of a metal and has a cross-sectional shape comprising a rectangular first region that determines a pattern width of the workpiece, and a second region that contacts the first region and intercepts application of etching beams to a sidewall of the first region during etching, as recited by independent claim 27.

The Office Action contends that claim 27 is anticipated by Fig. 2 of Gulde because it discloses:

an etching mask 3 for selectively etching a workpiece, wherein the etching mask 3 is made of metal 2 and has a cross-sectional shape comprising a rectangular first region that determines a pattern width of workpiece 1, and a

second region that intercepts application of etching beams (Fig. 2) to a sidewall of the first region during etching.

See the third paragraph of Item 3. (Emphasis added).

Contrary to this contention, however, Gulde discloses that layer 2 is the workpiece to be "structured" by a layer 3 acting as the mask (see, for example, the first and second sentences of the abstract in Gulde; see, also, column 1, lines 7-13; and see column 4, lines 52-57), and that layer 1 is the substrate, which is not disclosed as being worked on. Accordingly, it is unclear how substrate 1 can be construed as the workpiece. It is also unclear how layer 3 can intercept the application of etching beams to a sidewall of a first region (whatever region in Gulde corresponds to the first region in claim 27).

Accordingly, at least for this reason, Applicant submits that Gulde fails to anticipate independent claim 27. Claim 32 depends from claim 27 and, therefore, distinguishes over Gulde at least for the reason explained with respect to claim 27.

In view of the above, Applicant respectfully requests that the rejection of claims 27 and 32 be reconsidered and withdrawn.

CONCLUSION

In view of the foregoing amendments and remarks, Applicant submits that this application is in condition for allowance. Favorable reconsideration and prompt allowance of claims 27-37 are earnestly solicited.

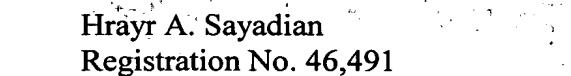
Should the Examiner believe that anything further would be desirable in order to place this application in better condition for allowance, the Examiner is invited to contact Applicant's undersigned representative at the telephone number listed below.

Respectfully submitted,



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Attachments:

Appendix
Amendment Transmittal Letter

Date: June 21, 2002

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DEPOSIT ACCOUNT USE AUTHORIZATION Please grant any extension necessary for entry; Charge any fee due to our Deposit Account No. 15-0461
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APPENDIX

Changes to Claims:

The following are marked-up versions of the amended claims:

27. (Amended) An etching mask for selectively etching a workpiece, wherein the etching mask is made of a metal and has a cross-sectional shape comprising a rectangular first region that determines a pattern width of the workpiece, and a second region that contacts the first region and intercepts application of etching beams to a sidewall of the first region during etching.

28. (Amended) An etching mask for selectively etching a workpiece, wherein the etching mask is made of a metal and has a cross-sectional shape comprising a rectangular first region that determines a pattern width of the workpiece, and a second region that intercepts application of etching beams to a sidewall of the first region during etching~~The etching mask according to claim 27, wherein the etching mask has a T-shaped cross section.~~

30. (Amended) An etching mask for selectively etching a workpiece, wherein the etching mask is made of a metal and has a cross-sectional shape comprising a rectangular first region that determines a pattern width of the workpiece, and a second region that intercepts application of etching beams to a sidewall of the first region during etching~~The etching mask according to claim 27, wherein comprising a cross section including the first region is a vertical bar having an end that contacts with a surface of the workpiece, and the second region is a lateral bar placed on another end of the vertical bar and having a width greater than a width of the vertical bar, wherein a pattern width of the workpiece is determined by the width of the vertical bar.~~